

What is claimed is:

1. An active matrix type liquid crystal display device comprising:
 - a pair of substrates;
 - a liquid crystal sealed between said pair of substrates;
 - a plurality of data lines and a plurality of scanning lines which are arranged so as to intersect each other on one surface of a first of said pair of substrates;
 - a switching element having an electric current path, one end of which is connected to a corresponding one of said data lines, and having a control terminal which is connected to a corresponding one of said scanning lines;
 - a pixel electrode which is provided above said data lines via an insulation film, and is connected to the other end of the electric current path of said switching element;
 - a common electrode which opposes said data lines via said insulation film, said common electrode having slits in portions overlapping said data lines to generate an electric field between said pixel electrode;
 - a black matrix which is arranged on a second of said pair of substrates in a predetermined pattern, said black matrix being covered by a flattening film:
 - a first conductive film provided on said flattening film so as to oppose said data lines via said slits, said first conductive film being set to a common electric potential with said common electrode, wherein said first conductive film overlaps said portions of said common electrode wherein said slits are formed, and said first conductive film overlaps said black matrix.
2. The active matrix type liquid crystal display device according to claim 1, wherein said first conductive film has a pattern which is almost the same as that of said black matrix.

3. The active matrix type liquid crystal display device according to claim 1, wherein said first conductive film is made of ITO (Indium Tin Oxide).

4. The active matrix type liquid crystal display device according to claim 3, wherein said first conductive film has a width narrower than a width of said black matrix and is made of an opaque material having a low resistance.

5. A method of manufacturing an active matrix type liquid crystal display device, said liquid crystal display device including: a pair of substrates, a thin film transistor which is provided on one of said pair of substrates, data lines which are connected to a drain of said thin film transistor, a pixel electrode which is connected to a source of said thin film transistor, and a common electrode which generates an electric field between said pixel electrode, said method comprising:

forming an insulation film which covers said data lines;

forming a first metal film on said insulation film;

forming said common electrode by patterning said first metal film, including forming slits in portions of said common electrode that overlap said data lines;

forming a black matrix having a predetermined pattern on one surface of the other one of said pair of substrates;

forming a flattening film on said black matrix; and

forming a first conductive film on said flattening film, said first conductive film opposing said data lines via said slits, wherein said first conductive film overlaps said portions of said common electrode wherein said slits are formed, and said first conductive film overlaps said black matrix.

6. The method of manufacturing an active matrix type liquid crystal display device according to claim 5, wherein in said forming said first conductive film, said first conductive film is formed in a pattern that is the same as that of said black matrix.

7. The method of manufacturing an active matrix type liquid crystal display device according to claim 5, wherein said forming a first conductive film includes forming said first conductive film by using ITO (Indium Tin Oxide).

8. The method of manufacturing an active matrix type liquid crystal display device according to claim 5, wherein said forming a first conductive film includes forming said first conductive film having a width narrower than said black matrix, by using an opaque material having a low resistance.